

PATENT  
0171-1063P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: OHSAWA, Youichi et al      Conf.:  
Appl. No.: NEW      Group:  
Filed: February 12, 2004      Examiner:  
For: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID  
GENERATORS, RESIST COMPOSITIONS, AND  
PATTERNING PROCESS

PRELIMINARY AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

February 12, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes:

Amendments to the Specification

Remarks